

|    | Hit<br>s | Search Text  | DBs   |
|----|----------|--|---|
| 22 | 2        | ((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (uniform\$3 or thin\$4 or etch\$4) same micron)<br>and<br>(((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 (liberat\$4 or generat\$4)) or PAG or photo\$8generat\$4) near9 (increas\$4 or var\$5 or chang\$4 adjust\$4 or alter\$4 or control\$4)) same (moiet\$4 or group or (function\$3 near4 group))) and ((fluoro\$4polymer\$4 or ((fluor\$4 or halogen) near9 (polymer or carbon)) or (SOG near6 (organic or resist))) same (pattern\$4 or lithograph\$6 or photolithograph\$8 or expos\$4 or mask)) | US-PPGPUB;<br>USPAT; EPO;<br>JPO; DERWENT;<br>IBM_TDB |

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|----|----------|---|--|
| 23 | 46       | <pre>((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same (coat\$4 or spin\$4coat\$4 or deposit\$4) same (uniform\$3 or thin\$4 or etch\$4) same (resolution or imag\$4 or thickness or micron)) and (((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 (liberat\$4 or generat\$4)) or PAG or photo\$8generat\$4) near9 (increas\$4 or var\$5 or chang\$4 adjust\$4 or alter\$4 or control\$4)) same (moiet\$4 or group or (function\$3 near4 group)))</pre> | US - PGPUB;<br>USPAT; EPO;<br>JPO; DERWENT;<br>IBM_TDB |